Mikko Ritala

List of Publications by Year
in descending order

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		8159	12233
543	26,809	76	133
papers	citations	h-index	g-index

565	565	565	17163
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Reaction mechanism studies on atomic layer deposition process of AlF3. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2022, 40, .	0.9	2
2	Ambient pressure x-ray photoelectron spectroscopy setup for synchrotron-based in situ and operando atomic layer deposition research. Review of Scientific Instruments, 2022, 93, 013905.	0.6	9
3	Atomic layer deposition of GdF3 thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2022, 40, .	0.9	4
4	Inter-laboratory workflow for forensic applications: Classification of car glass fragments. Forensic Science International, 2022, 333, 111216.	1.3	7
5	Molecular Layer Deposition of Thermally Stable Polybenzimidazoleâ€Like Thin Films and Nanostructures. Advanced Materials Interfaces, 2022, 9, .	1.9	1
6	Osteoblast Attachment on Titanium Coated with Hydroxyapatite by Atomic Layer Deposition. Biomolecules, 2022, 12, 654.	1.8	9
7	A low-temperature thermal ALD process for nickel utilizing dichlorobis(triethylphosphine)nickel(<scp>ii</scp>) and 1,4-bis(trimethylgermyl)-1,4-dihydropyrazine. Dalton Transactions, 2022, 51, 10898-10908.	1.6	4
8	Template-free hierarchical trimetallic oxide photocatalyst derived from organically modified ZnCuCo layered double hydroxide. Journal of Cleaner Production, 2022, 366, 132761.	4.6	15
9	Atomic Layer Deposition of CsI and CsPbI₃. Chemistry of Materials, 2022, 34, 6087-6097.	3.2	6
10	In Situ Positron Annihilation Spectroscopy Analysis on Lowâ€Temperature Irradiated Semiconductors, Challenges and Possibilities. Physica Status Solidi (A) Applications and Materials Science, 2021, 218, 2000232.	0.8	2
11	Sb-doped zirconium dioxide submicron fibers for separation of pertechnetate (TcO₄^{â€“}) from aqueous solutions. Separation Science and Technology, 2021, 56, 2338-2350.	1.3	4
12	Thermal gas-phase etching of titanium nitride (TiN) by thionyl chloride (SOCl2). Applied Surface Science, 2021, 540, 148309.	3.1	3
13	Effect of polyethylene wax/soy protein-based dispersion barrier coating on the physical, mechanical, and barrier characteristics of paperboards. Journal of Coatings Technology Research, 2021, 18, 247-257.	1.2	7
14	Role of ALD Al₂O₃ Surface Passivation on the Performance of p-Type Cu₂O Thin Film Transistors. ACS Applied Materials & Interfaces, 2021, 13, 4156-4164.	4.0	31
15	Novel electroblowing synthesis of tin dioxide and composite tin dioxide/silicon dioxide submicron fibers for cobalt(<scp>ii</scp>) uptake. RSC Advances, 2021, 11, 15245-15257.	1.7	5
16	Highly conductive and stable Co9S8 thin films by atomic layer deposition: from process development and film characterization to selective and epitaxial growth. Dalton Transactions, 2021, 50, 13264-13275.	1.6	0
17	Observed and Modeled Black Carbon Deposition and Sources in the Western Russian Arctic 1800â€“2014. Environmental Science & Technology, 2021, 55, 4368-4377.	4.6	9
18	Atomic layer deposition of TbF3 thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, .	0.9	5

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19	Atomic Layer Deposition of Insulating AlF3/Polyimide Nanolaminate Films. Coatings, 2021, 11, 355.	1.2	3
20	Synchronizing gas injections and time-resolved data acquisition for perturbation-enhanced APXPS experiments. Review of Scientific Instruments, 2021, 92, 044101.	0.6	11
21	Thermal Atomic Layer Etching of Aluminum Oxide (Al₂O₃) Using Sequential Exposures of Niobium Pentafluoride (NbF₅) and Carbon Tetrachloride (CCl₄): A Combined Experimental and Density Functional Theory Study of the Etch Mechanism. Chemistry of Materials, 2021, 33, 2883-2893.	3.2	11
22	Highly Material Selective and Selfâ€Aligned Photoâ€assisted Atomic Layer Deposition of Copper on Oxide Materials. Advanced Materials Interfaces, 2021, 8, 2100014.	1.9	6
23	Oxidative MLD of Conductive PEDOT Thin Films with EDOT and ReCl₅ as Precursors. ACS Omega, 2021, 6, 17545-17554.	1.6	10
24	Understanding the Stabilizing Effects of Nanoscale Metal Oxide and Liâ€“Metal Oxide Coatings on Lithium-Ion Battery Positive Electrode Materials. ACS Applied Materials & Interfaces, 2021, 13, 42773-42790.	4.0	18
25	Self-Aligned Thin-Film Patterning by Area-Selective Etching of Polymers. Coatings, 2021, 11, 1124.	1.2	3
26	Atomic Layer Deposition of 2D Metal Dichalcogenides for Electronics, Catalysis, Energy Storage, and Beyond. Advanced Materials Interfaces, 2021, 8, 2001677.	1.9	39
27	Combining Experimental and DFT Investigation of the Mechanism Involved in Thermal Etching of Titanium Nitride Using Alternate Exposures of NbF 5 and CCl 4 , or CCl 4 Only. Advanced Materials Interfaces, 2021, 8, 2101085.	1.9	3
28	Atomic Layer Deposition of GdF3 Thin Films. ECS Meeting Abstracts, 2021, MA2021-02, 878-878.	0.0	1
29	Al₂O₃ Thin Films Prepared by a Combined Thermalâ€Plasma Atomic Layer Deposition Process at Low Temperature for Encapsulation Applications. Physica Status Solidi (A) Applications and Materials Science, 2020, 217, 1900237.	0.8	4
30	Van der Waals epitaxy of continuous thin films of 2D materials using atomic layer deposition in low temperature and low vacuum conditions. 2D Materials, 2020, 7, 011003.	2.0	18
31	Ionic conductivity in LixTaOy thin films grown by atomic layer deposition. Electrochimica Acta, 2020, 361, 137019.	2.6	6
32	Controlling Atomic Layer Deposition of 2D Semiconductor SnS₂ by the Choice of Substrate. Advanced Materials Interfaces, 2020, 7, 2001046.	1.9	10
33	Atomic Layer Deposition of PbS Thin Films at Low Temperatures. Chemistry of Materials, 2020, 32, 8216-8228.	3.2	16
34	In Situ Reaction Mechanism Study on Atomic Layer Deposition of Intermetallic Co₃Sn₂ Thin Films. Chemistry of Materials, 2020, 32, 8120-8128.	3.2	6
35	Magnetic properties and resistive switching in mixture films and nanolaminates consisting of iron and silicon oxides grown by atomic layer deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, .	0.9	7
36	Area-Selective Molecular Layer Deposition of Polyimide on Cu through Cu-Catalyzed Formation of a Crystalline Interchain Polyimide. Chemistry of Materials, 2020, 32, 5073-5083.	3.2	17

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37	Effect of interstitial carbon on the evolution of early-stage irradiation damage in equi-atomic FeMnNiCoCr high-entropy alloys. Journal of Applied Physics, 2020, 127, .	1.1	24
38	Silicon oxide-niobium oxide mixture films and nanolaminates grown by atomic layer deposition from niobium pentaethoxide and hexakis(ethylamino) disilane. Nanotechnology, 2020, 31, 195713.	1.3	5
39	Preparation and in vivo evaluation of red blood cell membrane coated porous silicon nanoparticles implanted with 155Tb. Nuclear Medicine and Biology, 2020, 84-85, 102-110.	0.3	9
40	High-temperature X-ray scattering studies of atomic layer deposited IrO₂. Journal of Applied Crystallography, 2020, 53, 369-380.	1.9	2
41	Photocatalytic and Gas Sensitive Multiwalled Carbon Nanotube/TiO2-ZnO and ZnO-TiO2 Composites Prepared by Atomic Layer Deposition. Nanomaterials, 2020, 10, 252.	1.9	17
42	Electrospun sodium titanate fibres for fast and selective water purification. Environmental Technology (United Kingdom), 2019, 40, 3561-3567.	1.2	3
43	Atomic Layer Deposition of Emerging 2D Semiconductors, HfS₂ and ZrS₂, for Optoelectronics. Chemistry of Materials, 2019, 31, 5713-5724.	3.2	72
44	Submicron fibers as a morphological improvement of amorphous zirconium oxide particles and their utilization in antimonate (Sb(v)) removal. RSC Advances, 2019, 9, 22355-22365.	1.7	7
45	Atomic Layer Deposition of Photoconductive Cu₂O Thin Films. ACS Omega, 2019, 4, 11205-11214.	1.6	40
46	Nickel Germanide Thin Films by Atomic Layer Deposition. Chemistry of Materials, 2019, 31, 5314-5319.	3.2	7
47	Charge carrier dynamics in tantalum oxide overlayered and tantalum doped hematite photoanodes. Journal of Materials Chemistry A, 2019, 7, 3206-3215.	5.2	25
48	Titania Nanotubes/Hydroxyapatite Nanocomposites Produced with the Use of the Atomic Layer Deposition Technique: Estimation of Bioactivity and Nanomechanical Properties. Nanomaterials, 2019, 9, 123.	1.9	20
49	Comparative study on the use of novel heteroleptic cyclopentadienyl-based zirconium precursors with H2O and O3 for atomic layer deposition of ZrO2. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	0.9	7
50	Fully Automated Online Dynamic In-Tube Extraction for Continuous Sampling of Volatile Organic Compounds in Air. Analytical Chemistry, 2019, 91, 8507-8515.	3.2	18
51	Intercalation of Lithium Ions from Gaseous Precursors into Î²-MnO2 Thin Films Deposited by Atomic Layer Deposition. Journal of Physical Chemistry C, 2019, 123, 15802-15814.	1.5	11
52	Studies on solid state reactions of atomic layer deposited thin films of lithium carbonate with hafnia and zirconia. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	0.9	5
53	Atomic Layer Deposition of Nickel Nitride Thin Films using NiCl₂(TMPDA) and Tertâ€Butylhydrazine as Precursors. Physica Status Solidi (A) Applications and Materials Science, 2019, 216, 1900058.	0.8	6
54	Review Article: Atomic layer deposition of optoelectronic materials. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2019, 37, .	0.6	48

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55	Crystalline tungsten sulfide thin films by atomic layer deposition and mild annealing. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	0.9	15
56	Toward epitaxial ternary oxide multilayer device stacks by atomic layer deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	0.9	5
57	Low-Temperature Plasma-Enhanced Atomic Layer Deposition of SiO2 Using Carbon Dioxide. Nanoscale Research Letters, 2019, 14, 55.	3.1	7
58	Controlling the refractive index and third-order nonlinearity of polyimide/Ta2O5 nanolaminates for optical applications. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, 060908.	0.9	5
59	Photoassisted atomic layer deposition of oxides employing alkoxides as single-source precursors. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	0.9	7
60	Novel electroblowing synthesis of submicron zirconium dioxide fibers: effect of fiber structure on antimony(<scp>v</scp>) adsorption. Nanoscale Advances, 2019, 1, 4373-4383.	2.2	12
61	Atomic layer deposition of cobalt(II) oxide thin films from Co(BTSA)2(THF) and H2O. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	0.9	4
62	TiO₂ Photocatalyzed Oxidation of Drugs Studied by Laser Ablation Electrospray Ionization Mass Spectrometry. Journal of the American Society for Mass Spectrometry, 2019, 30, 639-646.	1.2	12
63	Atomic Layer Deposition of PbI₂ Thin Films. Chemistry of Materials, 2019, 31, 1101-1109.	3.2	49
64	Atomic Layer Deposition of Intermetallic Co₃Sn₂ and Ni₃Sn₂ Thin Films. Advanced Materials Interfaces, 2019, 6, 1801291.	1.9	15
65	Lowâ€Temperature Waferâ€Scale Deposition of Continuous 2D SnS₂ Films. Small, 2018, 14, e1800547.	5.2	48
66	Zeolitic imidazole Framework-8 (ZIF-8) fibers by gas-phase conversion of electroblown zinc oxide and aluminum doped zinc oxide fibers. Microporous and Mesoporous Materials, 2018, 267, 212-220.	2.2	16
67	Tracing grog and pots to reveal Neolithic Corded Ware Culture contacts in the Baltic Sea region (SEM-EDS, PIXE). Journal of Archaeological Science, 2018, 91, 77-91.	1.2	26
68	Atomic Layer Deposition of Rhenium Disulfide. Advanced Materials, 2018, 30, e1703622.	11.1	58
69	Metal oxide multilayer hard mask system for 3D nanofabrication. Nanotechnology, 2018, 29, 055301.	1.3	5
70	Towards space-grade 3D-printed, ALD-coated small satellite propulsion components for fluidics. Additive Manufacturing, 2018, 22, 31-37.	1.7	21
71	Patterned films by atomic layer deposition using Parafilm as a mask. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2018, 36, .	0.9	4
72	Atomic Layer Deposition of Molybdenum and Tungsten Oxide Thin Films Using Heteroleptic Imido-Amidinato Precursors: Process Development, Film Characterization, and Gas Sensing Properties. Chemistry of Materials, 2018, 30, 8690-8701.	3.2	26

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73	Atomic Layer Deposition and Properties of HfO₂-Al₂O₃ Nanolaminates. ECS Journal of Solid State Science and Technology, 2018, 7, P501-P508.	0.9	12
74	Atomic Layer Deposition and Performance of ZrO₂-Al₂O₃Thin Films. ECS Journal of Solid State Science and Technology, 2018, 7, P287-P294.	0.9	8
75	Atomic layer deposition of crystalline molybdenum oxide thin films and phase control by post-deposition annealing. Materials Today Chemistry, 2018, 9, 17-27.	1.7	44
76	Atomic layer deposition of lanthanum oxide with heteroleptic cyclopentadienyl-amidinate lanthanum precursor - Effect of the oxygen source on the film growth and properties. Thin Solid Films, 2018, 660, 199-206.	0.8	10
77	Rhenium Metal and Rhenium Nitride Thin Films Grown by Atomic Layer Deposition. Angewandte Chemie, 2018, 130, 14746-14750.	1.6	3
78	Adhesion and mechanical properties of nanocrystalline hydroxyapatite coating obtained by conversion of atomic layer-deposited calcium carbonate on titanium substrate. Journal of Materials Science: Materials in Medicine, 2018, 29, 111.	1.7	17
79	Rhenium Metal and Rhenium Nitride Thin Films Grown by Atomic Layer Deposition. Angewandte Chemie - International Edition, 2018, 57, 14538-14542.	7.2	21
80	In Honor of Professor Markku LeskelÃ. Chemistry of Materials, 2018, 30, 4469-4474.	3.2	1
81	Diamine Adduct of Cobalt(II) Chloride as a Precursor for Atomic Layer Deposition of Stoichiometric Cobalt(II) Oxide and Reduction Thereof to Cobalt Metal Thin Films. Chemistry of Materials, 2018, 30, 3499-3507.	3.2	27
82	Electroluminescent Phosphors â˜†. , 2018, , .		0
83	Metal Fluorides as Lithium-Ion Battery Materials: An Atomic Layer Deposition Perspective. Coatings, 2018, 8, 277.	1.2	35
84	Enhanced process and composition control for atomic layer deposition with lithium trimethylsilanolate. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	0.9	11
85	Atomic layer deposition and properties of mixed Ta2O5 and ZrO2 films. AIP Advances, 2017, 7, .	0.6	26
86	Potential gold(I) precursors evaluated for atomic layer deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	0.9	14
87	Surface modification of acetaminophen particles by atomic layer deposition. International Journal of Pharmaceutics, 2017, 525, 160-174.	2.6	40
88	Studies on Li3AlF6 thin film deposition utilizing conversion reactions of thin films. Thin Solid Films, 2017, 636, 26-33.	0.8	5
89	Atomic layer deposition of tin oxide thin films from bis[bis(trimethylsilyl)amino]tin(II) with ozone and water. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	0.9	23
90	Atomic Layer Deposition of Crystalline MoS₂ Thin Films: New Molybdenum Precursor for Lowâ€Temperature Film Growth. Advanced Materials Interfaces, 2017, 4, 1700123.	1.9	98

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91	As2S3 thin films deposited by atomic layer deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, 01B114.	0.9	9
92	TiO₂ Photocatalysisâ€“DESI-MS Rotating Array Platform for High-Throughput Investigation of Oxidation Reactions. Analytical Chemistry, 2017, 89, 11214-11218.	3.2	7
93	Atomic Layer Deposition of Zinc Glutarate Thin Films. Advanced Materials Interfaces, 2017, 4, 1700512.	1.9	3
94	Low-Temperature Atomic Layer Deposition of Cobalt Oxide as an Effective Catalyst for Photoelectrochemical Water-Splitting Devices. Chemistry of Materials, 2017, 29, 5796-5805.	3.2	43
95	Admittance memory cycles of Ta<inf>2</inf>O<inf>5</inf>-ZrO<inf>2</inf>-based RRAM devices. , 2017, , .		0
96	Structure-Dependent Mechanical Properties of ALD-Grown Nanocrystalline BiFeO₃Multiferroics. Journal of Nanomaterials, 2016, 2016, 1-7.	1.5	7
97	The role of surface preparation in corrosion protection of copper with nanometer-thick ALD alumina coatings. Applied Surface Science, 2016, 387, 1054-1061.	3.1	24
98	Heteroleptic Cyclopentadienyl-Amidinate Precursors for Atomic Layer Deposition (ALD) of Y, Pr, Gd, and Dy Oxide Thin Films. Chemistry of Materials, 2016, 28, 5440-5449.	3.2	25
99	Atomic Layer Deposition of Iridium Thin Films Using Sequential Oxygen and Hydrogen Pulses. Journal of Physical Chemistry C, 2016, 120, 15235-15243.	1.5	26
100	Low-temperature atomic layer deposition of copper(II) oxide thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2016, 34, .	0.9	18
101	Scalable Route to the Fabrication of CH₃NH₃PbI₃ Perovskite Thin Films by Electrodeposition and Vapor Conversion. ACS Omega, 2016, 1, 1296-1306.	1.6	44
102	Atomic Layer Deposition (ALD) grown thin films for ultra-fine pitch pixel detectors. Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment, 2016, 831, 2-6.	0.7	9
103	MANOS performance dependence on ALD Al2O3 oxidation source. Microelectronic Engineering, 2016, 159, 127-131.	1.1	1
104	Nucleation and Conformality of Iridium and Iridium Oxide Thin Films Grown by Atomic Layer Deposition. Langmuir, 2016, 32, 10559-10569.	1.6	31
105	Coating and functionalization of high density ion track structures by atomic layer deposition. Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment, 2016, 832, 254-258.	0.7	1
106	Integration of atomic layer deposited nanolaminates on silicon waveguides (Conference) Tj ETQq0 0 0 rgBT /Overlock 10 Tf 50 142 Td (		0
107	Rapid production of bioactive hydroxyapatite fibers via electroblowing. Journal of the European Ceramic Society, 2016, 36, 3219-3224.	2.8	29
108	Nuclear reaction analysis for H, Li, Be, B, C, N, O and F with an RBS check. Nuclear Instruments & Methods in Physics Research B, 2016, 371, 211-215.	0.6	32

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109	Bismuth iron oxide thin films using atomic layer deposition of alternating bismuth oxide and iron oxide layers. Thin Solid Films, 2016, 611, 78-87.	0.8	19
110	Atomic layer deposition of aluminum oxide on modified steel substrates. Surface and Coatings Technology, 2016, 304, 1-8.	2.2	11
111	Electric and Magnetic Properties of ALD-Grown BiFeO₃ Films. Journal of Physical Chemistry C, 2016, 120, 7313-7322.	1.5	35
112	Interfacial native oxide effects on the corrosion protection of copper coated with ALD alumina. Electrochimica Acta, 2016, 193, 7-15.	2.6	25
113	Corrosion protection of aluminium by ultra-thin atomic layer deposited alumina coatings. Corrosion Science, 2016, 106, 16-24.	3.0	68
114	Alkylsilyl compounds as enablers of atomic layer deposition: analysis of (Et3Si)3As through the GaAs process. Journal of Materials Chemistry C, 2016, 4, 449-454.	2.7	3
115	Electrochemical and Surface Analysis of the Corrosion Protection of Copper by Nanometer-Thick Alumina Coatings Prepared by Atomic Layer Deposition. Journal of the Electrochemical Society, 2015, 162, C377-C384.	1.3	25
116	MANOS erase performance dependence on nitrogen annealing conditions. Materials Research Society Symposia Proceedings, 2015, 1729, 15-20.	0.1	0
117	Osteoclasts in the interface with electrospun hydroxyapatite. Colloids and Surfaces B: Biointerfaces, 2015, 135, 774-783.	2.5	17
118	Resistless fabrication of embedded nanochannels by FIB patterning, wet etching and atomic layer deposition. , 2015, , .		0
119	Needleless electrospinning with twisted wire spinneret. Nanotechnology, 2015, 26, 025301.	1.3	57
120	Atomic Layer Deposition and Characterization of Bi₂Te₃ Thin Films. Journal of Physical Chemistry A, 2015, 119, 2298-2306.	1.1	24
121	Studies on atomic layer deposition of IRMOF-8 thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2015, 33, .	0.9	23
122	Impedance spectroscopy study of the unipolar and bipolar resistive switching states of atomic layer deposited polycrystalline ZrO₂ thin films. Physica Status Solidi (A) Applications and Materials Science, 2015, 212, 751-766.	0.8	20
123	Atomic Layer Deposition of AlF₃ Thin Films Using Halide Precursors. Chemistry of Materials, 2015, 27, 604-611.	3.2	33
124	Selective etching of focused gallium ion beam implanted regions from silicon as a nanofabrication method. Nanotechnology, 2015, 26, 265304.	1.3	6
125	Atomic layer deposition of zirconium dioxide from zirconium tetrachloride and ozone. Thin Solid Films, 2015, 589, 597-604.	0.8	22
126	Inert ambient annealing effect on MANOS capacitor memory characteristics. Nanotechnology, 2015, 26, 134004.	1.3	21

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127	Following the dynamics of matter with femtosecond precision using the X-ray streaking method. Scientific Reports, 2015, 5, 7644.	1.6	24
128	Osteogenic and osteoclastogenic differentiation of co-cultured cells in polylactic acidâ€“nanohydroxyapatite fiber scaffolds. Journal of Biotechnology, 2015, 204, 53-62.	1.9	54
129	(Et₃Si)₂Se as a precursor for atomic layer deposition: growth analysis of thermoelectric Bi₂Se₃. Journal of Materials Chemistry C, 2015, 3, 4820-4828.	2.7	16
130	Nitrogen induced modifications of MANOS memory properties. Nuclear Instruments & Methods in Physics Research B, 2015, 365, 61-65.	0.6	1
131	High-quality slot waveguide ring resonator based on atomic layer deposition. Proceedings of SPIE, 2015, , .	0.8	1
132	High Aspect-Ratio Iridium-Coated Nanopillars for Highly Reproducible Surface-Enhanced Raman Scattering (SERS). ACS Applied Materials & Interfaces, 2015, 7, 11452-11459.	4.0	27
133	High resolution double-sided diffractive optics for hard X-ray microscopy. Optics Express, 2015, 23, 776.	1.7	46
134	Slot waveguide ring resonators coated by an atomic layer deposited organic/inorganic nanolaminate. Optics Express, 2015, 23, 26940.	1.7	14
135	Conduction and stability of holmium titanium oxide thin films grown by atomic layer deposition. Thin Solid Films, 2015, 591, 55-59.	0.8	1
136	Mechanical properties of aluminum, zirconium, hafnium and tantalum oxides and their nanolaminates grown by atomic layer deposition. Surface and Coatings Technology, 2015, 282, 36-42.	2.2	31
137	Atomic Layer Deposition. , 2014, , 101-123.		37
138	PCRAM. , 2014, , 123-148.		0
139	Magnetic Properties of Polycrystalline Bismuth Ferrite Thin Films Grown by Atomic Layer Deposition. Journal of Physical Chemistry Letters, 2014, 5, 4319-4323.	2.1	30
140	Cyclopentadienyl Precursors for the Atomic Layer Deposition of Erbium Oxide Thin Films. Chemical Vapor Deposition, 2014, 20, 217-223.	1.4	8
141	Atomic-scale engineering of multifunctional nano-sized materials and films. Physica Status Solidi (A) Applications and Materials Science, 2014, 211, 249-250.	0.8	0
142	Atomic Layer Deposition of Groups 4 and 5 Transition Metal Oxide Thin Films: Focus on Heteroleptic Precursors. Chemical Vapor Deposition, 2014, 20, 189-208.	1.4	32
143	Resistive Switching Behavior and Electrical Properties of TiO2:Ho2O3 and HoTiOx Based MIM Capacitors. Materials Research Society Symposia Proceedings, 2014, 1691, 43.	0.1	1
144	In situ reaction mechanism studies on the Ti(NMe2)2(OiPr)2-D2O and Ti(OiPr)3[MeC(NiPr)2]-D2O atomic layer deposition processes. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2014, 32, 01A121.	0.9	2

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145	Voltage-Dependent Properties of Titanium Dioxide Nanotubes Anodized in Solutions Containing EDTA. Journal of the Electrochemical Society, 2014, 161, E61-E65.	1.3	4
146	Atomic Layer Deposition of Noble Metals and Their Oxides. Chemistry of Materials, 2014, 26, 786-801.	3.2	308
147	Single-parameter model for the post-breakdown conduction characteristics of HoTiOx-based MIM capacitors. Microelectronics Reliability, 2014, 54, 1707-1711.	0.9	0
148	Combining focused ion beam and atomic layer deposition in nanostructure fabrication. Nanotechnology, 2014, 25, 115302.	1.3	2
149	Electrospinning of calcium carbonate fibers and their conversion to nanocrystalline hydroxyapatite. Materials Science and Engineering C, 2014, 45, 469-476.	3.8	13
150	Holmium and titanium oxide nanolaminates by atomic layer deposition. Thin Solid Films, 2014, 565, 165-171.	0.8	10
151	Preparation and bioactive properties of nanocrystalline hydroxyapatite thin films obtained by conversion of atomic layer deposited calcium carbonate. Biointerphases, 2014, 9, 031008.	0.6	15
152	Heteroleptic Precursors for Atomic Layer Deposition. ECS Transactions, 2014, 64, 221-232.	0.3	3
153	Atomic Layer Deposition of TiO₂ and ZrO₂ Thin Films Using Heteroleptic Guanidinate Precursors. Chemical Vapor Deposition, 2014, 20, 209-216.	1.4	9
154	Interface control of atomic layer deposited oxide coatings by filtered cathodic arc deposited sublayers for improved corrosion protection. Materials Chemistry and Physics, 2014, 147, 895-907.	2.0	10
155	Modification of Hematite Electronic Properties with Trimethyl Aluminum to Enhance the Efficiency of Photoelectrodes. Journal of Physical Chemistry Letters, 2014, 5, 3582-3587.	2.1	21
156	Sealing of Hard CrN and DLC Coatings with Atomic Layer Deposition. ACS Applied Materials & Interfaces, 2014, 6, 1893-1901.	4.0	61
157	Corrosion properties of steel protected by nanometre-thick oxide coatings. Corrosion Science, 2014, 82, 208-217.	3.0	29
158	Atomic Layer Deposition, Characterization, and Growth Mechanistic Studies of TiO₂ Thin Films. Langmuir, 2014, 30, 7395-7404.	1.6	13
159	Holmium titanium oxide thin films grown by atomic layer deposition. Thin Solid Films, 2014, 565, 261-266.	0.8	12
160	Study of atomic layer deposited Zr<scp>O</scp>₂ and Zr<scp>O</scp>₂/<scp>T</scp>i<scp>O</scp>₂ films for resistive switching application. Physica Status Solidi (A) Applications and Materials Science, 2014, 211, 301-309.	0.8	15
161	X-ray ptychographic computed tomography at 16â€…nm isotropic 3D resolution. Scientific Reports, 2014, 4, 3857.	1.6	281
162	Continuous-Wave Laser Annealing of a Si/SiO₂ Superlattice: Effect of the Ambient Atmosphere and Exposure Period. Science of Advanced Materials, 2014, 6, 1000-1010.	0.1	3

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